

a1
Conced

1 7. (Amended) The plasma display panel of Claim 1,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric
3 glass material.

a2

1 13. (Amended) The plasma display panel of Claim 8,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric
3 glass material.

a3

1 17. (Amended) The plasma display panel of Claim 14,
2 wherein the metal or the metal oxide that coats the surface of each Ag particle
3 forms a layer with an average thickness in a range of 01 μm to 1 μm inclusive.

1 18. (Amended) The plasma display panel of Claim 14,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric
3 glass material.

a4

1 21. (Amended) The plasma display panel of Claim 19,
2 wherein the first plate, or both the first plate and the second plate are glass plates.

1 22. (Amended) A display apparatus comprising:
2 the plasma display panel of Claim 1; and
3 a driving circuit that drives the plasma display panel.

a5 1 31. (Amended) The manufacturing method for a plasma display panel of Claim 29,
2 wherein in the electrode formation step, the electrodes made of the silver alloy are
3 formed, by forming the silver alloy into a film by a sputtering method, and patterning the formed
4 film.

1 32. (Amended) The manufacturing method for a plasma display panel of Claim 29,
2 wherein in the electrode formation step, the electrodes made of the silver alloy are
3 formed, by (a) forming a film containing the silver alloy and a glass frit, (b) patterning the
4 formed film, and (c) baking the patterned film.

a6 1 34. (Amended) The manufacturing method for a plasma display panel of Claim 29,
2 wherein in the electrode formation step, the electrodes made of the silver alloy are
3 formed, by applying a paste containing the silver alloy and a glass frit in electrode shapes, and
4 baking the applied paste.

a7 1 48. (Amended) The manufacturing method for a substrate for use in a plasma display
2 panel of Claim 46,
3 wherein in the etching step, the glass plate is etched by impregnating the surface
4 of the glass plate with a liquid containing fluorine.

1 49. (Amended) The manufacturing method for a substrate for use in a plasma display
2 panel of Claim 46,
3 wherein in the etching step, the glass plate is etched so that a concentration of
4 metal ions that exist in a vicinity of a surface of the etched substrate is 1000ppm or less, the
5 metal ions possessing reducing action on Ag ions.

27
1 50. (Amended) The manufacturing method for a substrate for use in a plasma display
2 panel of Claim 46,

3 wherein in the etching step, the glass plate is etched so that a total concentration
4 of tin with less than four valence electrons, manganese with less than four valence electrons, iron
5 with less than two valence electrons, and indium with less than two valence electrons that exist
6 in a vicinity of a surface of the etched substrate is 1000ppm or less.

1 51. (Amended) The manufacturing method for a substrate for use in a plasma display
2 panel of Claim 46,

3 wherein the etching step is followed by a polishing step for polishing the surface
4 of the etched substrate.

28
5 55. (Amended) The manufacturing method for a substrate for use in a plasma display
6 panel of Claim 52,

7 wherein in the deactivating step, the glass plate is processed so that a total
8 concentration of tin with less than four valence electrons, manganese with less than four valence
9 electrons, iron with less than two valence electrons, and indium with less than two valence
10 electrons that exist in a region of 5μm in depth from a surface of the substrate is 1000ppm or
11 less.

Please add the following newly-drafted Claims 56-90.

29
1 56. (New) The plasma display panel of Claim 2,

2 wherein the first electrodes are constructed by forming each electrode on a
3 transparent electrode film.

a9
Cont'd

1 57. (New) The plasma display panel of Claim 3,
2 wherein the first electrodes are constructed by forming each electrode on a
3 transparent electrode film.

1 58. (New) The plasma display panel of Claim 4,
2 wherein the first electrodes are constructed by forming each electrode on a
3 transparent electrode film.

1 59. (New) The plasma display panel of Claim 5,
2 wherein the first electrodes are constructed by forming each electrode on a
3 transparent electrode film.

1 60. (New) The plasma display panel of Claim 2,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric glass
3 material.

1 61. (New) The plasma display panel of Claim 3,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric glass
3 material.

62. (New) The plasma display panel of Claim 4,
wherein the first electrodes are covered with a dielectric layer made of a dielectric glass
material.

29
Cont'd

63. (New) The plasma display panel of Claim 5,
wherein the first electrodes are covered with a dielectric layer made of a dielectric glass
material.

1 64. (New) The plasma display panel of Claim 9,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric
3 glass material.

0
1
2
3
4
5
6
7
8
9
T
E
S
T
0
1
2
3
4
5
6
7
8
9
T
E
S
T

65. (New) The plasma display panel of Claim 10,
wherein the first electrodes are covered with a dielectric layer made of a dielectric
glass material.

66. (New) The plasma display panel of Claim 11,
wherein the first electrodes are covered with a dielectric layer made of a dielectric
glass material.

1 67. (New) The plasma display panel of Claim 12,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric
3 glass material.

29
Conf'd

1 68. (New) The plasma display panel of Claim 15,
2 wherein the metal or the metal oxide that coats the surface of each Ag particle
3 forms a layer with an average thickness in a range of 01 μm to 1 μm inclusive.

1 69. (New) The plasma display panel of Claim 16,
2 wherein the metal or the metal oxide that coats the surface of each Ag particle
3 forms a layer with an average thickness in a range of 01 μm to 1 μm inclusive.

1 70. (New) The plasma display panel of Claim 15,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric
3 glass material.

1 71. (New) The plasma display panel of Claim 16,
2 wherein the first electrodes are covered with a dielectric layer made of a dielectric
3 glass material.

1 72. (New) The plasma display panel of Claim 20,
2 wherein the first plate, or both the first plate and the second plate are glass plates.

1 73. (New) A display apparatus comprising:
2 the plasma display panel of Claim 3; and
3 a driving circuit that drives the plasma display panel.

1 74. (New) A display apparatus comprising:
2 the plasma display panel of Claim 8; and
3 a driving circuit that drives the plasma display panel.

29
Conf'd

1
2
3
4
5
6
7
8
9
10
11
12
13
14
15
16
17
18
19
20
21
22
23
24
25
26
27
28
29
30
31
32
33
34
35
36
37
38
39
40
41
42
43
44
45
46
47
48
49
50
51
52
53
54
55
56
57
58
59
60
61
62
63
64
65
66
67
68
69
70
71
72
73
74
75
76
77
78
79
80
81
82
83
84
85
86
87
88
89
90
91
92
93
94
95
96
97
98
99
100

75. (New) A display apparatus comprising:
the plasma display panel of Claim 10; and
a driving circuit that drives the plasma display panel.

76. (New) A display apparatus comprising:
the plasma display panel of Claim 14; and
a driving circuit that drives the plasma display panel.

77. (New) A display apparatus comprising:
the plasma display panel of Claim 19; and
a driving circuit that drives the plasma display panel.

78. (New) A display apparatus comprising:
the plasma display panel of Claim 20; and
a driving circuit that drives the plasma display panel.

79. (New) The manufacturing method for a plasma display panel of Claim 30,
wherein in the electrode formation step, the electrodes made of the silver alloy are
formed, by forming the silver alloy into a film by a sputtering method, and patterning the formed
film.

80. (New) The manufacturing method for a plasma display panel of Claim 30,
wherein in the electrode formation step, the electrodes made of the silver alloy are
formed, by (a) forming a film containing the silver alloy and a glass frit, (b) patterning the
formed film, and (c) baking the patterned film.

ag
Conf'd

1 81. (New) The manufacturing method for a plasma display panel of Claim 30,
2 wherein in the electrode formation step, the electrodes made of the silver alloy are
3 formed, by applying a paste containing the silver alloy and a glass frit in electrode shapes, and
4 baking the applied paste.

1 82. (New) The manufacturing method for a substrate for use in a plasma display panel
2 of Claim 47,
3 wherein in the etching step, the glass plate is etched by impregnating the surface
4 of the glass plate with a liquid containing fluorine.

1 83. (New) The manufacturing method for a substrate for use in a plasma display
2 panel of Claim 47,
3 wherein in the etching step, the glass plate is etched so that a concentration of
4 metal ions that exist in a vicinity of a surface of the etched substrate is 1000ppm or less, the
5 metal ions possessing reducing action on Ag ions.

1 84. (New) The manufacturing method for a substrate for use in a plasma display
2 panel of Claim 48,
3 wherein in the etching step, the glass plate is etched so that a concentration of
4 metal ions that exist in a vicinity of a surface of the etched substrate is 1000ppm or less, the
5 metal ions possessing reducing action on Ag ions.

1 85. (New) The manufacturing method for a substrate for use in a plasma display panel
2 of Claim 47,
3 wherein in the etching step, the glass plate is etched so that a total concentration

4 of tin with less than four valence electrons, manganese with less than four valence electrons, iron
5 with less than two valence electrons, and indium with less than two valence electrons that exist
6 in a vicinity of a surface of the etched substrate is 1000ppm or less.

1 86. (New) The manufacturing method for a substrate for use in a plasma display panel
2 of Claim 48,

3 wherein in the etching step, the glass plate is etched so that a total concentration
4 of tin with less than four valence electrons, manganese with less than four valence electrons, iron
5 with less than two valence electrons, and indium with less than two valence electrons that exist
6 in a vicinity of a surface of the etched substrate is 1000ppm or less.

1 87. (New) The manufacturing method for a substrate for use in a plasma display panel
2 of Claim 47,

3 wherein the etching step is followed by a polishing step for polishing the surface
4 of the etched substrate.

1 88. (New) The manufacturing method for a substrate for use in a plasma display panel
2 of Claim 48,

3 wherein the etching step is followed by a polishing step for polishing the surface
4 of the etched substrate.

1 89. (New) The manufacturing method for a substrate for use in a plasma display panel
2 of Claim 53,

3 wherein in the deactivating step, the glass plate is processed so that a total
4 concentration of tin with less than four valence electrons, manganese with less than four valence

29
Conceded

5 electrons, iron with less than two valence electrons, and indium with less than two valence
6 electrons that exist in a region of 5 μ m in depth from a surface of the substrate is 1000ppm or
7 less.

90. (New) The manufacturing method for a substrate for use in a plasma display panel
of Claim 54,

wherein in the deactivating step, the glass plate is processed so that a total
concentration of tin with less than four valence electrons, manganese with less than four valence
electrons, iron with less than two valence electrons, and indium with less than two valence
electrons that exist in a region of 5 μ m in depth from a surface of the substrate is 1000ppm or
less.
